



TSMC-01-972

February 27, 2004

To: Commissioner for Patents
P.O.Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/725,810 12/02/03 |
Fei-Gwo Tsai
METHOD OF THE ADJUSTABLE MATCHING
MAP SYSTEM IN LITHOGRAPHY
| _____ |

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
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P.O. Box 1450, Alexandria, VA 22313-1450, on March), 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

SPBQ 3/1/04

U.S. Patent 5,044,750 to Shamble, "Method for Checking Lithography Critical Dimensions," discloses a method for checking alignment of a pattern in a photoresist layer.

U.S. Patent 6,352,323 to Rives, "Media Presentation System," discloses a method of aligning a mask level to marks in two previous layers.

U.S. Patent 4,929,083 to Brunner, "Focus and Overlay Characterization and Optimization for Photolithographic Exposure," describes an in-situ overlay method.

U.S. Patent 6,288,556 to Sato et al., "Method of Electrical Measurement of Misregistration of Patterns," discusses measuring electrical resistance to determine the amount of misregistration between two patterned levels.

U.S. Patent 6,342,323 to Ma et al., "Alignment Methodology for Lithography," discloses an alignment methodology for lithography.

Sincerely,

A handwritten signature in black ink, appearing to read 'SBA', with a long horizontal flourish extending to the right.

Stephen B. Ackerman,
Reg. No. 37761

Form PTO-1449

Document Number (Specimen)

Application Number

TSMC-01-972

10/725,810

Applicant

Fei-Gwo Tsai

Filing Date

12/02/03

Group Art Unit

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

(Use several sheets if necessary)

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILED DATE & APPROPRIATE
	5044750	9/3/91	Shamble	356	372	8/13/90
	6352323	3/5/02	Rives	312	324	12/31/98
	4929083	5/29/90	Brunner	356	400	3/20/89
	6288556	9/11/01	Sato et al.	324	715	12/3/98
	6342323	1/29/02	Ma et al.	430	22	3/13/00

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
					YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Portion of Pages, Etc.)

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.